	T A 11 41 - 54		_
	Application No.	Applicant(s)	
No. 45 - 1 P. A.H. 1 1994	10/707,120	WANG ET AL.	
Notice of Allowability	Examiner	Art Unit	_
	Dung V Nguyen	3723	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in ) or other appropriate comministing the comministing in the c	n this application. If not included unication will be mailed in due course. THIS	e
1. This communication is responsive to			
2. The allowed claim(s) is/are <u>1-18</u> .			
3.   The drawings filed on are accepted by the Examine	er.		
<ul> <li>4. ☐ Acknowledgment is made of a claim for foreign priority upon a) ☐ All b) ☐ Some* c) ☐ None of the:</li> <li>1. ☐ Certified copies of the priority documents have</li> <li>2. ☐ Certified copies of the priority documents have</li> <li>3. ☐ Copies of the certified copies of the priority documents have a longer large la</li></ul>	e been received. e been received in Application	on No	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file MENT of this application.	e a reply complying with the requirements	
5. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EX	AMINER'S AMENDMENT or NOTICE OF r declaration is deficient.	
6. X CORRECTED DRAWINGS ( as "replacement sheets") mu	st be submitted.		
(a) 🛛 including changes required by the Notice of Draftsper		v ( PTO-948) attached	
1) 🛮 hereto or 2) 🔲 to Paper No./Mail Date	·	•	
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment o	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on t the header according to 37 CF	he drawings in the front (not the back) of FR 1.121(d).	
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	osit of BIOLOGICAL MAT FOR THE DEPOSIT OF BIO	ERIAL must be submitted. Note the DLOGICAL MATERIAL.	
Attachment(s)			
1. Notice of References Cited (PTO-892)		formal Patent Application (PTO-152)	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ∐ Interview S Paper No	ummary (PTO-413), /Mail Date	
3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date 11/21/03	08), 7. ⊠ Examiner's	Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit		Statement of Reasons for Allowance	
of Biological Material	9. 🗌 Other	<b>-</b> •	
	Dung	vom hynym	
	=	N NGUYEN Examiner	

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## **EXAMINER'S AMENDMENT**

- 1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.
- 2. The application has been amended as follows:

Delete the abstract and insert therefore:

A chemical-mechanical polishing (CMP) system and method includes pumping polishing slurry from a CMP apparatus through a sampling tube to an endpoint detection apparatus during a polishing operation, and flushing the sampling tube while a polishing operation is not in progress. The flushing of the sampling tube is commenced in accordance with a control signal from the endpoint detection apparatus terminating the polishing operation; the flushing is terminated in accordance with a starting signal to the CMP apparatus. The pump, which pumps a sample of slurry into the endpoint detection apparatus, continuously pumps slurry and/or water. Clogging of the slurry sampling tube is thus eliminated, thereby ensuring robust operation of the CMP apparatus.

Contamination of the sampling tube is also avoided, so that the system may reliably provide sensitive endpoint detection and process control, even when a film of low pattern density is polished.

## **REASONS FOR ALLOWANCE**

3. The following is an examiner's statement of reasons for allowance: prior art of record considered as a whole alone or in combination neither anticipates nor renders

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obvious, providing a slurry flushing apparatus for flushing slurry from the sampling tube while a polishing operation is not in progress, in combination with the rest of the limitations in claim 1; prior art of record considered as a whole alone or in combination neither anticipates nor renders obvious, a first flow control valve connected to the slurry sampling tube for controlling a flow of water into the slurry sampling tube to flush slurry from the sampling tube while the polishing operation is not in progress and a second flow control valve connected to the first control valve by a flush tube for controlling the flow of water to the first control valve, in combination with the rest of the limitations in claim 11.

- 4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."
- 5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dung V Nguyen whose telephone number is 703-305-0036. The examiner can normally be reached on M-F, 6:30-3:00.
- 6. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph J Hail can be reached on 703-308-2687. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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7. Information regarding the status of an application may be obtained from the

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Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

DVN

August 12, 2004

DUNG VAN NGUYEN PRIMARY EXAMINER

Sung van hyngen